

Title (en)  
CONTINUOUS KILN AND THERMAL TREATMENT OR THERMAL CHEMICAL PROCESSING METHOD

Title (de)  
DURCHLAUFOFEN UND WÄRMEBEHANDLUNGS- ODER WÄRMEBEHANDLUNGSVERFAHREN

Title (fr)  
FOUR CONTINU ET PROCÉDÉ DE TRAITEMENT THERMIQUE OU THERMOCHIMIQUE

Publication  
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Application  
**EP 21899587 A 20210715**

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Abstract (en)  
[origin: EP4249840A1] A continuous kiln and a thermal treatment or thermal chemical processing method, relating to the field of lithium-ion battery material processing. The continuous kiln comprises a kiln, an airflow supply and exhaust device, and an airflow control device. The airflow supply and exhaust device and the airflow control device work in conjunction to control an atmosphere in a furnace chamber of the kiln. Since air supply nozzles and air exhaust nozzles in the airflow supply and exhaust device are arranged opposite to each other, transverse airflow perpendicular to the length direction of the kiln may be formed, and the internal atmosphere may be kept stable.

IPC 8 full level  
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[X] DE 3138232 A1 19830428 - KRAMER CARL, et al

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